

NOVEL MONOMERS CONTAINING AN OXEPAN-2-ONE GROUP,
PHOTORESIST COMPOSITIONS COMPRISING POLYMERS
PREPARED FROM THE MONOMERS, METHODS FOR PREPARING
THE COMPOSITIONS, AND METHODS FOR FORMING PHOTORESIST
PATTERNS USING THE COMPOSITIONS

ABSTRACT OF THE DISCLOSURE

Disclosed herein is a novel norbornene, acrylate or methacrylate monomer as a photoresist monomer containing an oxepan-2-one group. Further disclosed are photoresist compositions comprising a polymer prepared from the monomer, methods for preparing the photoresist compositions, and methods for forming photoresist patterns using the photoresist compositions.